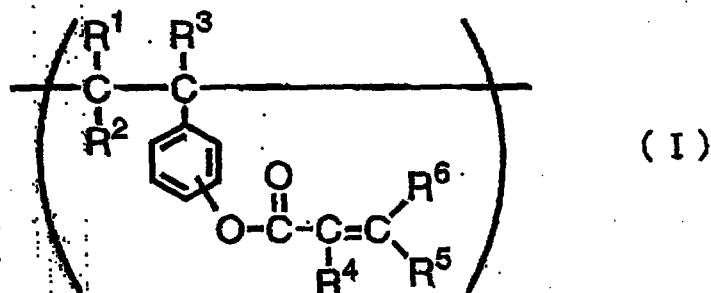


ABSTRACT

A photoresist composition which is particularly useful as a chemical amplification type photoresist is provided, wherein the photoresist composition contains a resin having a structural unit represented by the following formula (I) :



This Sheet Has Been Replaced



wherein R^1 , R^2 and R^3 each independently represents a hydrogen atom or an alkyl group having 1 to 4 carbon atoms; R^4 represents a hydrogen atom, an alkyl group having 1 to 4 carbon atoms or an alkoxy group having 1 to 4 carbon atoms and R^5 represents a hydrogen atom, alkyl group or aryl group, or R^4 and R^5 join together to form a ring, which may be heterocyclic; and R^6 represents a hydrogen atom, an alkyl group having 1 to 4 carbon atoms, an alkoxy group having 1 to 4 carbon atoms or a hydroxyl group.

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